

April 20 (Mon.)		Room A (F203+204)	Room B (F205+206)	April 21 (Tue.)		Room A (F203+204)
8:40 - 8:50	Opening			8:40 - 10:10	Session 11	
8:50 - 10:20	Session 1 Opening Session <i>Keynote</i> Presenter: Dr. Klaus Schuegraf (Intel Corporation) <i>Invited Talk</i> Presenter: Prof. Takeo Watanabe (University of Hyogo) Presenter: Dr. Yu Cao (ASML)				Writing I <i>Invited Talk</i> Presenter: Dr. Elmar Platzgummer (IMS Nanofabrication GmbH)	
10:20 - 10:40	Break			10:10 - 10:30	Break	
10:40 - 12:00	Session 2 Curvilinear Data Handling		10:40 - 12:00 FPD	10:30 - 12:00	Session 12 Writing II <i>Invited Talk</i> Presenter: Prof. Takahiro Kozawa (Osaka University)	
12:00 - 13:20	Lunch Break			12:00 - 13:20	Lunch Break	
13:20 - 14:20	Session 4 Mask Process Correction (MPC)		13:20 - 14:00 Session 5 EUV Pellicle	13:20 - 14:50	Session 13 EUV Special Session <i>Invited Talk</i> Presenter: Dr. Jan van Schoot (ASML) Presenter: Dr. Bartosz Bilski (Carl Zeiss SMT GmbH) Presenter: Mr. Hiroki Miyai (Lasertec Corporation)	
14:20 - 15:00	Session 7 Machine Learning		14:00 - 15:00 Session 6 Material, Process & Metrology			
15:00 - 15:20	Break			14:50 - 15:10	Break	
15:20 - 15:50	Session 8 Invited Session Presenter: Mr. Aki Fujimura (D2S, Inc.)			15:10 - 16:40	Session 14 EUV <i>Invited Talk</i> Presenter: Dr. Frank Jan Timmermans (ASML)	
15:50 - 17:00	Session 9 NIL <i>Invited Talk</i> Presenter: Dr. Douglas Resnick (Canon Nanotechnologies, Inc.)			16:40 - 17:00	Break	
17:00 - 18:20	Session 10 Poster Session (Venue: Foyer) 10A: Mask Process 10B: Writing 10C: Metrology 10D: EUV 10E: Overlay 10F: Strategy 10G: NGL 10S: Mask / Lithography Related Technologies in Academia			17:00 - 18:40	Session 15 Inspection	
18:20 - 20:20	Banquet			18:40 - 18:50	Closing	